

List of Reference Symbols



- 100 Integrated circuit
- 101 Silicon substrate
- 102 Contact-making element
- 103 First field-effect transistor
- 104 Second field-effect transistor
- 105 Gate region
- 106 Gate region
- 200 First layout view of an integrated circuit
- 201 First field-effect transistor
- 202 Second field-effect transistor
- 203 Common gate line
- 203a First gate component
- 203b Second component
- 203c First course direction
- 203d Second course direction
- 203e Third course direction
- 203f Fourth course direction
- 204 Active region
- 204a First course direction
- 204b Second course direction
- 205 Active region
- 205a First course direction
- 205b Second course direction
- 206 First square contact-making element
- 207 Second square contact-making element
- 208 Third square contact-making element
- 300 Second layout view of an integrated circuit
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- 301a Third course direction
- 301b Fourth course direction
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- 302a Third course direction
- 302b Fourth course direction
- 303 Third rectangular contact-making element
- 303a Third course direction
- 303b Fourth course direction
- 401 Lithography device

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407 Aligning optical arrangement
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409 Lens
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